



Reliance Industries Limited

P O L Y P R O P Y L E N E

REPOL AS12000N ULTRA HIGH MELT FLOW POLYPROPYLENE HOMOPOLYMER

Provisional Technical Data Sheet

REPOL AS12000N ultra-high melt flow, narrow molecular weight polypropylene homopolymer resin is suitable for melt blown applications. This material is available in spherical particle form. Repol AS12000N is recommended for use in nonwoven melt blowing process.

Property	ASTM Test Method	Unit	Typical Value*
Melt Flow Index (230°C / 2.16kg)	RIL Method	g/10 min	1200
Density	D 1505	g/cc	0.9
Melting Temperature (DSC)	D 3418	°C	161-165

* Typical values, not to be taken as specification.

Grade Features: Repol AS12000N is designed to provide;

- Good melt blown process ability
- Fine microfibres
- Excellent barrier properties
- Reduced process energy demand

Applications: Melt blown nonwoven fabrics for Absorption & Filtration, Hygiene & Medical Disposables, Wipes & Tissues

Regulatory Information: Meets the requirements stipulated in IS 10910 on “Specification for Polypropylene and its copolymers for safe use in contact with foodstuffs, pharmaceuticals, and drinking water”. Additives incorporated in this grade conform to the positive list of constituents as prescribed in IS 10909. The grade and the additives incorporated in it also comply with the FDA: CFR Title 21,177.1520, Olefin polymers.

Storage, Transport & Handling: Bags should be stored in a cool, well ventilated place at ambient temperature or below 40°C and protected from UV / direct sunlight. Keep away from heat and direct sunlight. This product should be kept away from naked flames and other sources of ignition. Control dust formation during handling. Take precautionary measures against static discharges.

REPOL is the registered trademark for Polypropylene from Reliance Industries Limited

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